ALD Finland November Networking 2026 Posters

1. A. Almasri, Atomic Layer Deposition of Nickel Oxide as Hole Transport Layer for Perovskite Solar Cells, University of Helsinki
2. O. Partanen, Achieving Area-Selective ALD/MLD with Polymer Substrates, Aalto University
3. A. Bogdanova, Influence of initial ALD pulse sequence on surface reactions and electrochemical performance of NMC811, Aalto University
4. O. Dobrozhan, Atomic Layer Deposition of ZnO on Nanostructured Cu12Sb4S13 for Thermoelectric Applications
5. A. Heidari, Atomic layer deposition of AgX (X= Cl, Br, I) thin films, University of Helsinki
6. N. Heikkinen, An atomic layer deposition diffusion–reaction model for porous media with different particle geometries, VTT Technical Research Centre of Finland
7. S. Levorin, Enhancing Second Harmonic Generation in ALD-Grown Ferroelectric Superlattices for Programmable Photonics, Aalto University
8. J. Linjala, Anion Engineering of Atomic Layer Deposited Zn(O,S) Thin Films for Next-Generation Solar Cells, Aalto University
9. T. Malmelin, Aalto University

10. S. Pakseresht, From Coatings to Stable Interfaces: Atomic Layer Deposition for Lithium Metal, Aalto University
11. J. Pekkanen, Multi-Organic Sensitized Luminescence in Atomic/Molecular Layer Deposited Europium-Organic Thin Films, Aalto University
12. J. Razavi, Surface wettability control of cellulose via chemical vapor deposition: Towards fluorine-free hydrophobic coatings, Aalto University
13. J. A. Velasco, Atomic layer deposition in high-aspect-ratio features: how changing reactant exposure from excess to limiting affects the film thickness profile, Aalto University
14. M. Chaudhary, Instrumentation for Thin-film Stack Characterization at the Atomic-scale, Aalto University
15. S. Gosalvez, ALD SiO2 provides efficient Ge surface passivation with a tailorable charge polarity, Aalto University
16. I. Sundas, Area selective atomic layer deposition (AS-ALD) of metal films using small molecule inhibitors (SMIs), University of Helsinki
17. L. Lahtiluoma, ALD dielectrics enable ohmic contact formation, Aalto University
18. M. Mäkinen, The growth reactions of hybrid zincone ALD/MLD thin films, Aalto University
19. E. Varttila, Automating the data processing of SEM-EDS measurements from film grown on LHAR-structures, Aalto University